



Atty. Dkt. No. 017447-0194

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Koichi WATANABE et al.

Title: SPUTTERING TARGET AND PROCESS FOR PRODUCING Si OXIDE FILM THEREWITH

Appl. No.: 10/573,406

International 9/22/2004

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REPLY UNDER 37 CFR 1.116

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Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This communication is responsive to the Final Office Action dated June 22, 2010, concerning the above-referenced patent application.

Applicant has enclosed with this amendment a Petition for Extension of Time to make this response timely.

Remarks begin on page 2 of this document.